

INFORMATION DISCLOSURE STATEMENT BY APPLICANT <i>(use as many sheets as necessary)</i>		<i>Complete if Known</i>	
		Application Number	10-7CCG205
		Filing Date	
		First Named Inventor	Shahid Rauf et al.
		Group Art Unit	
		Examiner Name	
Sheet	1	of	
		Attorney Docket Number	SC13121TP

U. S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. ¹	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number -Kind Code ² (if known)			
Opdy	AA	4,957,834	09/18/1990	Matsuda <i>et al.</i>	_____
Opdy	AB	5,691,090	11/25/1997	Isao <i>et al.</i>	_____
Opdy	AC	6,524,755	02/25/2003	Jin <i>et al.</i>	_____

FOREIGN PATENT DOCUMENTS						
Examiner's Initials*	Cite No. ¹	Foreign Patent Document	Publication Date	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
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gray	AD	EP 0 668 539 A2	08/23/1995	Dove et al.		

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No. 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ²
	AE	Constantine <i>et al.</i> , "ICP Quartz Etch Uniformity Improvement for Phase Shift Mask Fabrication," <i>Part of the SPIE Conference on Photomask and X-Ray Mask Technology V</i> , Kawasaki, Japan, SPIE, Vol. 3412, April 1998, pp. 220-	
	AF	Dahm <i>et al.</i> , "Quartz Etching for Phase Shifting Masks," <i>Microelectronic Engineering</i> , 1995, Vol. 27, pp. 263-266.	
	AG	Wu <i>et al.</i> , "CF ₄ /O ₂ Plasma Simulation and Comparison with Quartz Etch Experiment," <i>Photomask and Next-Generation Lithography Mask Technology VIII</i> , Hiroichi Kawahira, Editor, <i>Proceedings of SPIE</i> , 2001, Vol. 4409, pp. 409-417.	
	AH	Zeze <i>et al.</i> , "Reactive Ion Etching of Quartz and Pyrex for Microelectronic Applications," <i>Journal of Applied Physics</i> , October 2002, Vol. 92, No. 7, pp. 3624-3629.	

Examiner Signature	George Gundrean	Date Considered	3-05'
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